



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Akshey Seghal

Application No.: 10/620,895

Filed: July 16, 2003

For: COMPOSITIONS AND METHOD FOR  
REMOVING PHOTORESIST AND/OR  
RESIST RESIDUE AT PRESSURES  
RANGING FROM AMBIENT TO  
SUPERCRITICAL

Confirmation No.: 8934

Group Art Unit: 1746

Examiner: Bibi Sharidan Carrillo

**RESPONSE TO FINAL OFFICE ACTION  
MAILED JANUARY 4, 2005**

353 Sacramento St., Suite 2200  
San Francisco, CA 94111  
(415) 772-4900

M/S RCE  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited  
with the United States Postal Service as First Class Mail in an  
envelope, addressed to: Commissioner for Patents, P.O.  
Box 1450, Alexandria, VA 22313-1450 on May 3, 2005.  
STALLMAN & POLLOCK LLP

Dated: 05/3/2005

By:

*Georgia K. Stith*  
Georgia K. Stith

Sir:

In response to the Final Office Action mailed January 4, 2005, and in accordance with the  
accompanying **Request for Continued Examination** and One-Month Extension of Time, please  
amend the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this  
paper.

**Remarks/Arguments** begin on page 10 of this paper.

05/06/2005 WASFAW1 00000044 10620895

02 FC:2251

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Atty Docket No.: SCP-9410